

App. Serial No.: 10/017,458
Atty. Docket No.: 0011-051

IN THE CLAIMS

Please amend the claims to read as follows:

1. (currently amended) A method for creating a dummy metal fill pattern near functional circuitry, comprising:
 - [[a.]] creating a margin area around the functional circuitry;
selecting a dummy metal fill pattern of alternative functional circuitry;
 - [[b.]] trimming [[a]] the dummy metal fill pattern to the margin area to create a trimmed fill pattern; and
 - [[c.]] overlaying said trimmed fill pattern and the functional circuitry [[; and]]
~~wherein the dummy fill pattern is an example of an alternative functional circuitry.~~
2. (currently amended) The method for creating a dummy metal fill pattern of claim 1, and further including:
 - removing excess metal between step b and step e from the dummy metal fill pattern.
3. (original) The method for creating a dummy metal fill pattern of claim 2, wherein:
 - the excess metal is at least one metal sliver.
4. (currently amended) The method for creating a dummy metal fill pattern of claim 3, wherein:
 - the metal sliver is a thin strip of metal created when the margin area is removed from the dummy metal fill pattern.
- Claim 5 (canceled)
6. (previously amended) The method for creating a dummy metal fill pattern of claim 1, wherein:
 - the alternative functional circuitry is selected to be alike to that near the functional circuitry.

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7. (previously amended) The method for creating a dummy metal fill pattern of claim 1, wherein:

the alternative functional circuitry is a selected portion of functional circuitry from a metal layer on which the dummy metal fill pattern is to be used.

8. (original) The method for creating a dummy metal fill pattern of claim 1, wherein:

the dummy metal fill pattern is created on a metal layer of an LCOS array.

9. (original) The method for creating a dummy metal fill pattern of claim 1, wherein:

the dummy metal fill pattern is created on a layer under a mirror layer of an LCOS array.

10. (original) The method for creating a dummy metal fill pattern of claim 1, wherein:

the dummy metal fill pattern is created on a layer of a reflective LCOS array.

11. (canceled)

12. (canceled)

13. (original) The method for creating a dummy metal fill pattern of claim 1, wherein:

said margin area is created by growing the area of the functional circuitry.

Claims 14-22 (withdrawn)

23. (original) A method for providing dummy fill in a LCOS array, comprising:

selecting a metal fill pattern from functional circuitry on a layer of the array; and

filling an unfilled area with the metal fill pattern.

24. (original) The method for providing dummy fill of claim 23, and further including:

filling a partially filled area with a portion of the metal fill pattern.